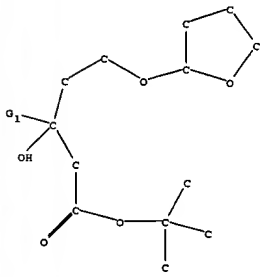
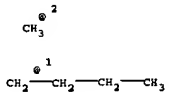
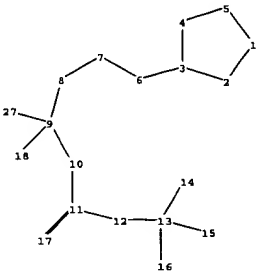
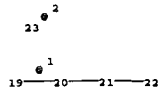
C:\Program Files\Stnexp\Queries\09940665.str









STN-CAS Search
Do Not Remove!

chain nodes :
6 7 8 9 10 11 12 13 14 15 16 17 18 19 20 21 22 23 27
ring nodes :
1 2 3 4 5
chain bonds :
3-6 6-7 7-8 8-9 9-10 9-18 9-27 10-11 11-12 11-17 12-13 13-14 13-15 13-16
19-20 20-21 21-22
ring bonds :
1-2 1-5 2-3 3-4 4-5
exact/norm bonds :
1-2 1-5 2-3 3-4 3-6 4-5 6-7 9-18 9-27 11-12 11-17 12-13
exact bonds :
7-8 8-9 9-10 10-11 13-14 13-15 13-16 19-20 20-21 21-22

G1:[*1],[*2]

Match level :
1:Atom 2:Atom 3:Atom 4:Atom 5:Atom 6:CLASS 7:CLASS 8:CLASS 9:CLASS 10:CLASS
11:CLASS 12:CLASS 13:CLASS 14:CLASS 15:CLASS 16:CLASS 17:CLASS 18:CLASS 19:CLASS
20:CLASS 21:CLASS 22:CLASS 23:CLASS 27:CLASS

L2 ANSWER 1 OF 422 REGISTRY COPYRIGHT 2003 ACS
RN 508693-53-6 REGISTRY
CN **Gamma-butyrolactone receptor protein (Streptomyces avermitilis strain MA-4680 gene avaR) (9CI)** (CA INDEX NAME)
OTHER NAMES:
CN GenBank BAC71417
CN GenBank BAC71417 (Translated from: GenBank AP005036)
FS PROTEIN SEQUENCE
MF Unspecified
CI MAN
SR GenBank
LC STN Files: CA, CAPLUS

*** STRUCTURE DIAGRAM IS NOT AVAILABLE ***
*** USE 'SQD' OR 'SQIDE' FORMATS TO DISPLAY SEQUENCE ***
1 REFERENCES IN FILE CA (1957 TO DATE)
1 REFERENCES IN FILE CAPLUS (1957 TO DATE)

=> d his

(FILE 'HOME' ENTERED AT 15:58:22 ON 10 JUN 2003)

FILE 'REGISTRY' ENTERED AT 15:58:43 ON 10 JUN 2003
L1 0 S GAMMA-BUTROLACTONE
L2 422 S GAMMA-BUTYROLACTONE

=> d 1

L2 ANSWER 1 OF 422 REGISTRY COPYRIGHT 2003 ACS
RN 508693-53-6 REGISTRY
CN **Gamma-butyrolactone receptor protein (Streptomyces avermitilis strain MA-4680 gene avaR) (9CI)** (CA INDEX NAME)
OTHER NAMES:
CN GenBank BAC71417
CN GenBank BAC71417 (Translated from: GenBank AP005036)
FS PROTEIN SEQUENCE
MF Unspecified
CI MAN
SR GenBank
LC STN Files: CA, CAPLUS

*** STRUCTURE DIAGRAM IS NOT AVAILABLE ***
*** USE 'SQD' OR 'SQIDE' FORMATS TO DISPLAY SEQUENCE ***
1 REFERENCES IN FILE CA (1957 TO DATE)
1 REFERENCES IN FILE CAPLUS (1957 TO DATE)

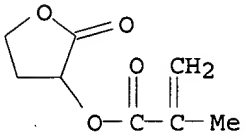
=> d 5

L2 ANSWER 5 OF 422 REGISTRY COPYRIGHT 2003 ACS
RN 499203-67-7 REGISTRY
CN 2-Propenoic acid, 2-methyl-, 2-hydroxypropyl ester, polymer with phenylmethyl 2-methyl-2-propenoate and tetrahydro-2-oxo-3-furanyl 2-methyl-2-propenoate (9CI) (CA INDEX NAME)
OTHER NAMES:
CN **Benzyl methacrylate-2-hydroxypropyl methacrylate-.alpha.-methacryloyloxy-.gamma.-butyrolactone copolymer**
MF (C11 H12 O2 . C8 H10 O4 . C7 H12 O3)x
CI PMS
PCT Polyacrylic, Polyester, Polyester formed
SR CA
LC STN Files: CA, CAPLUS

γ-butyrolactone methacrylate

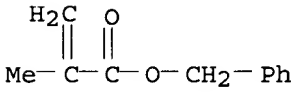
CM 1

CRN 195000-66-9
CMF C8 H10 O4



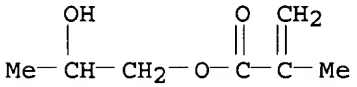
CM 2

CRN 2495-37-6
CMF C11 H12 O2



CM 3

CRN 923-26-2
CMF C7 H12 O3



2 REFERENCES IN FILE CA (1957 TO DATE)
2 REFERENCES IN FILE CAPLUS (1957 TO DATE)

=> FILE REG

COST IN U.S. DOLLARS	SINCE FILE ENTRY	TOTAL SESSION
FULL ESTIMATED COST	24.80	25.01

FILE 'REGISTRY' ENTERED AT 16:00:16 ON 10 JUN 2003

Property values tagged with IC are from the ZIC/VINITI data file provided by InfoChem.

STRUCTURE FILE UPDATES: 9 JUN 2003 HIGHEST RN 528266-88-8
DICTIONARY FILE UPDATES: 9 JUN 2003 HIGHEST RN 528266-88-8

TSCA INFORMATION NOW CURRENT THROUGH JANUARY 6, 2003

Please note that search-term pricing does apply when conducting SmartSELECT searches.

Crossover limits have been increased. See HELP CROSSOVER for details.

Experimental and calculated property data are now available. See HELP PROPERTIES for more information. See STNote 27, Searching Properties in the CAS Registry File, for complete details:
http://www.cas.org/ONLINE/STN/STNOTES/stnotes27.pdf

=> STR 195000-66-9

:END

L3 STRUCTURE CREATED

=> S L3 EXA SAM

SAMPLE SEARCH INITIATED 16:00:20 FILE 'REGISTRY'
SAMPLE SCREEN SEARCH COMPLETED - 0 TO ITERATE

100.0% PROCESSED 0 ITERATIONS 0 ANSWERS
SEARCH TIME: 00.00.01

FULL FILE PROJECTIONS: ONLINE **COMPLETE**
BATCH **COMPLETE**
PROJECTED ITERATIONS: 0 TO 0
PROJECTED ANSWERS: 0 TO 0

L4 0 SEA EXA SAM L3

=>

=>
NO ANSWERS WERE FOUND

=> FIL REGISTRY

COST IN U.S. DOLLARS	SINCE FILE ENTRY	TOTAL SESSION
FULL ESTIMATED COST	0.40	25.41

FILE 'REGISTRY' ENTERED AT 16:00:32 ON 10 JUN 2003
USE IS SUBJECT TO THE TERMS OF YOUR STN CUSTOMER AGREEMENT.
PLEASE SEE "HELP USAGETERMS" FOR DETAILS.

Property values tagged with IC are from the ZIC/VINITI data file provided by InfoChem.

STRUCTURE FILE UPDATES: 9 JUN 2003 HIGHEST RN 528266-88-8
DICTIONARY FILE UPDATES: 9 JUN 2003 HIGHEST RN 528266-88-8

TSCA INFORMATION NOW CURRENT THROUGH JANUARY 6, 2003

Please note that search-term pricing does apply when conducting SmartSELECT searches.

Crossover limits have been increased. See HELP CROSSOVER for details.

Experimental and calculated property data are now available. See HELP PROPERTIES for more information. See STNote 27, Searching Properties in the CAS Registry File, for complete details:
http://www.cas.org/ONLINE/STN/STNOTES/stnotes27.pdf

=> S 195000-66-9/RN

```
L5            1 195000-66-9/RN

=> SET NOTICE 1 DISPLAY

NOTICE SET TO 1 U.S. DOLLAR FOR DISPLAY COMMAND
SET COMMAND COMPLETED

=> D L5 RN CCN 1-

YOU HAVE REQUESTED DATA FROM 1 ANSWERS - CONTINUE? Y/(N):y
THE ESTIMATED COST FOR THIS REQUEST IS 1.68 U.S. DOLLARS
DO YOU WANT TO CONTINUE WITH THIS REQUEST? (Y)/N:y

L5   ANSWER 1 OF 1  REGISTRY  COPYRIGHT 2003 ACS
RN   195000-66-9  REGISTRY
CN   2-Propenoic acid, 2-methyl-, tetrahydro-2-oxo-3-furanyl ester (9CI)  (CA
     INDEX NAME)
OTHER NAMES:
CN   .alpha.-Methacryloyloxy-.gamma.-butyrolactone


=> SET NOTICE LOGIN DISPLAY

NOTICE SET TO OFF  FOR DISPLAY COMMAND
SET COMMAND COMPLETED

=>

=> d l1 d9
L1 HAS NO ANSWERS
L1            0 SEA FILE=REGISTRY ABB=ON  PLU=ON  GAMMA-BUTROLACTONE


=> d his

     (FILE 'HOME' ENTERED AT 15:58:22 ON 10 JUN 2003)

     FILE 'REGISTRY' ENTERED AT 15:58:43 ON 10 JUN 2003
L1            0 S GAMMA-BUTROLACTONE
L2          422 S GAMMA-BUTYROLACTONE

     FILE 'REGISTRY' ENTERED AT 16:00:16 ON 10 JUN 2003
L3              STR 195000-66-9
L4            0 S L3 EXA SAM

     FILE 'REGISTRY' ENTERED AT 16:00:32 ON 10 JUN 2003
L5            1 S 195000-66-9/RN
                SET NOTICE 1 DISPLAY
                SET NOTICE LOGIN DISPLAY

=> file reg
COST IN U.S. DOLLARS                          SINCE FILE      TOTAL
                                                 ENTRY    SESSION
FULL ESTIMATED COST                               2.48      27.89

FILE 'REGISTRY' ENTERED AT 16:01:26 ON 10 JUN 2003
USE IS SUBJECT TO THE TERMS OF YOUR STN CUSTOMER AGREEMENT.
PLEASE SEE "HELP USAGETERMS" FOR DETAILS.
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Property values tagged with IC are from the ZIC/VINITI data file
provided by InfoChem.
```

STRUCTURE FILE UPDATES: 9 JUN 2003 HIGHEST RN 528266-88-8
DICTIONARY FILE UPDATES: 9 JUN 2003 HIGHEST RN 528266-88-8

TSCA INFORMATION NOW CURRENT THROUGH JANUARY 6, 2003

Please note that search-term pricing does apply when conducting SmartSELECT searches.

Crossover limits have been increased. See HELP CROSSOVER for details.

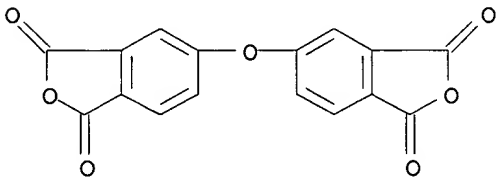
Experimental and calculated property data are now available. See HELP PROPERTIES for more information. See STNote 27, Searching Properties in the CAS Registry File, for complete details:
http://www.cas.org/ONLINE/STN/STNOTES/stnotes27.pdf

=> d l2 10

L2 ANSWER 10 OF 422 REGISTRY COPYRIGHT 2003 ACS
RN 469897-99-2 REGISTRY
CN 2-Propenoic acid, 2-methyl-, 2-hydroxyethyl ester, polymer with 1H,3H-benzo[1,2-c:4,5-c']difuran-1,3,5,7-tetrone, dihydro-2(3H)-furanone, 4,4'-oxybis[benzenamine] and 5,5'-oxybis[1,3-isobenzofurandione] (9CI) (CA INDEX NAME)
OTHER NAMES:
CN **.gamma.-Butyrolactone-4,4'-diaminodiphenyl ether-3,3',4,4'-diphenyl ether tetracarboxylic acid dianhydride-2-hydroxyethyl methacrylate-pyromellitic anhydride copolymer**
MF (C16 H6 O7 . C12 H12 N2 O . C10 H2 O6 . C6 H10 O3 . C4 H6 O2)x
CI PMS
PCT Polyacrylic, Polyamic acid, Polyamic acid formed, Polyester, Polyester formed, Polyether, Polyimide, Polyimide formed
SR CA
LC STN Files: CA, CAPLUS

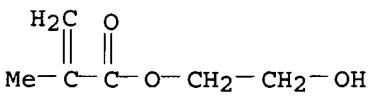
CM 1

CRN 1823-59-2
CMF C16 H6 O7



CM 2

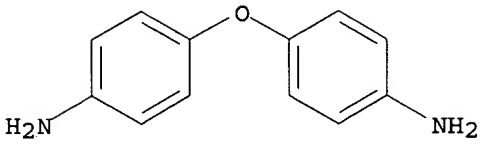
CRN 868-77-9
CMF C6 H10 O3



CM 3

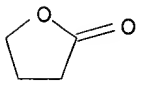
CRN 101-80-4

CMF C12 H12 N2 O



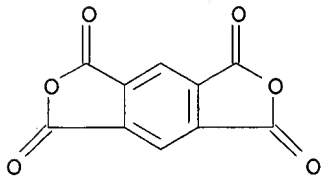
CM 4

CRN 96-48-0
CMF C4 H6 O2



CM 5

CRN 89-32-7
CMF C10 H2 O6

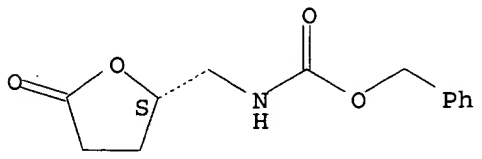


1 REFERENCES IN FILE CA (1957 TO DATE)
1 REFERENCES IN FILE CAPLUS (1957 TO DATE)

=> d l2 3

L2 ANSWER 3 OF 422 REGISTRY COPYRIGHT 2003 ACS
RN 501948-09-0 REGISTRY
CN Carbamic acid, [[(2S)-tetrahydro-5-oxo-2-furanyl]methyl]-, phenylmethyl ester (9CI) (CA INDEX NAME)
OTHER NAMES:
CN **N-(Benzyloxycarbonyl)-.gamma.-aminomethyl-.gamma.-butyrolactone**
FS STEREOSEARCH
MF C13 H15 N O4
SR CA
LC STN Files: CA, CAPLUS, CASREACT

Absolute stereochemistry.



PROPERTY DATA AVAILABLE IN THE 'PROP' FORMAT

1 REFERENCES IN FILE CA (1957 TO DATE)
1 REFERENCES IN FILE CAPLUS (1957 TO DATE)

=> file reg
COST IN U.S. DOLLARS | SINCE FILE ENTRY | TOTAL SESSION
FULL ESTIMATED COST | 3.76 | 31.65

FILE 'REGISTRY' ENTERED AT 16:02:03 ON 10 JUN 2003
USE IS SUBJECT TO THE TERMS OF YOUR STN CUSTOMER AGREEMENT.
PLEASE SEE "HELP USAGETERMS" FOR DETAILS.

Property values tagged with IC are from the ZIC/VINITI data file provided by InfoChem.

STRUCTURE FILE UPDATES: 9 JUN 2003 HIGHEST RN 528266-88-8
DICTIONARY FILE UPDATES: 9 JUN 2003 HIGHEST RN 528266-88-8

TSCA INFORMATION NOW CURRENT THROUGH JANUARY 6, 2003

Please note that search-term pricing does apply when conducting SmartSELECT searches.

Crossover limits have been increased. See HELP CROSSOVER for details.

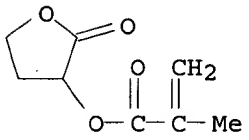
Experimental and calculated property data are now available. See HELP PROPERTIES for more information. See STNote 27, Searching Properties in the CAS Registry File, for complete details:
http://www.cas.org/ONLINE/STN/STNOTES/stnotes27.pdf

```
=> s gamma-butyrolactone methacrylate
        118094 GAMMA
             1 GAMMAS
        118094 GAMMA
                  (GAMMA OR GAMMAS)
           631 BUTYROLACTONE
         39272 METHACRYLATE
            10 METHACRYLATES
         39272 METHACRYLATE
                  (METHACRYLATE OR METHACRYLATES)
L6           2 GAMMA-BUTYROLACTONE METHACRYLATE
                  (GAMMA(W)BUTYROLACTONE(W)METHACRYLATE)

=> d

L6   ANSWER 1 OF 2  REGISTRY  COPYRIGHT 2003 ACS
RN   195000-67-0  REGISTRY
CN   2-Propenoic acid, 2-methyl-, 2-methyltricyclo[3.3.1.13,7]dec-2-yl ester,
     polymer with tetrahydro-2-oxo-3-furanyl 2-methyl-2-propenoate (9CI)  (CA
     INDEX NAME)
OTHER CA INDEX NAMES:
CN   2-Propenoic acid, 2-methyl-, tetrahydro-2-oxo-3-furanyl ester, polymer
     with 2-methyltricyclo[3.3.1.13,7]dec-2-yl 2-methyl-2-propenoate (9CI)
OTHER NAMES:
CN   .alpha.-Methacryloyloxy-.gamma.-butyrolactone-2-methyl-2-adamantyl
     methacrylate copolymer
CN   .gamma.-Butyrolacton-2-yl methacrylate-2-methyl-2-adamantyl methacrylate
     copolymer
CN   .gamma.-Butyrolactone methacrylate-2-methyladamantyl methacrylate
```

copolymer
DR 443892-48-6
MF (C15 H22 O2 . C8 H10 O4)x
CI PMS
PCT Polyacrylic, Polyester, Polyester formed
SR CA
LC STN Files: CA, CAPLUS, TOXCENTER, USPATFULL

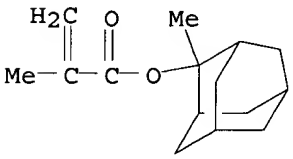
CM 1

CRN 195000-66-9
CMF C8 H10 O4



CM 2

CRN 177080-67-0
CMF C15 H22 O2



42 REFERENCES IN FILE CA (1957 TO DATE)
42 REFERENCES IN FILE CAPLUS (1957 TO DATE)

```
=> s 2-methyladamantyl methacrylate
      15320244 2
            18 METHYLADAMANTYL
         39272 METHACRYLATE
            10 METHACRYLATES
         39272 METHACRYLATE
                  (METHACRYLATE OR METHACRYLATES)
L7           7 2-METHYLADAMANTYL METHACRYLATE
                  (2(W)METHYLADAMANTYL(W)METHACRYLATE)

=> d his

     (FILE 'HOME' ENTERED AT 15:58:22 ON 10 JUN 2003)

     FILE 'REGISTRY' ENTERED AT 15:58:43 ON 10 JUN 2003
L1           0 S GAMMA-BUTROLACTONE
L2         422 S GAMMA-BUTYROLACTONE

     FILE 'REGISTRY' ENTERED AT 16:00:16 ON 10 JUN 2003
L3             STR 195000-66-9
L4           0 S L3 EXA SAM

     FILE 'REGISTRY' ENTERED AT 16:00:32 ON 10 JUN 2003
L5           1 S 195000-66-9/RN
```

SET NOTICE 1 DISPLAY
SET NOTICE LOGIN DISPLAY

FILE 'REGISTRY' ENTERED AT 16:01:26 ON 10 JUN 2003

FILE 'REGISTRY' ENTERED AT 16:02:03 ON 10 JUN 2003
L6 2 S GAMMA-BUTYROLACTONE METHACRYLATE
L7 7 S 2-METHYLADAMANTYL METHACRYLATE

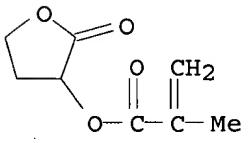
=> s l6 and l7
L8 1 L6 AND L7

=> d l8

L8 ANSWER 1 OF 1 REGISTRY COPYRIGHT 2003 ACS
RN 195000-67-0 REGISTRY
CN 2-Propenoic acid, 2-methyl-, 2-methyltricyclo[3.3.1.13,7]dec-2-yl ester, polymer with tetrahydro-2-oxo-3-furanyl 2-methyl-2-propenoate (9CI) (CA INDEX NAME)
OTHER CA INDEX NAMES:
CN 2-Propenoic acid, 2-methyl-, tetrahydro-2-oxo-3-furanyl ester, polymer with 2-methyltricyclo[3.3.1.13,7]dec-2-yl 2-methyl-2-propenoate (9CI)
OTHER NAMES:
CN .alpha.-Methacryloyloxy-.gamma.-butyrolactone-2-methyl-2-adamantyl methacrylate copolymer
CN .gamma.-Butyrolacton-2-yl methacrylate-2-methyl-2-adamantyl methacrylate copolymer
CN **.gamma.-Butyrolactone methacrylate-2-methyladamantyl methacrylate copolymer**
DR 443892-48-6
MF (C15 H22 O2 . C8 H10 O4)x
CI PMS
PCT Polyacrylic, Polyester, Polyester formed
SR CA
LC STN Files: CA, CAPLUS, TOXCENTER, USPATFULL

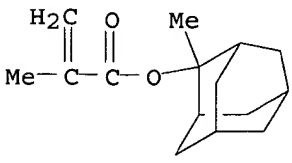
CM 1

CRN 195000-66-9
CMF C8 H10 O4



CM 2

CRN 177080-67-0
CMF C15 H22 O2



```
              42 REFERENCES IN FILE CA (1957 TO DATE)
              42 REFERENCES IN FILE CAPLUS (1957 TO DATE)


=> FIL CAPLUS HCAPLUS USPATFULL USPAT2
COST IN U.S. DOLLARS                                SINCE FILE      TOTAL
                                                         ENTRY    SESSION
FULL ESTIMATED COST                                      29.48      61.13

FILE 'CAPLUS' ENTERED AT 16:03:03 ON 10 JUN 2003
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FILE 'HCAPLUS' ENTERED AT 16:03:03 ON 10 JUN 2003
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FILE 'USPATFULL' ENTERED AT 16:03:03 ON 10 JUN 2003
CA INDEXING COPYRIGHT (C) 2003 AMERICAN CHEMICAL SOCIETY (ACS)

FILE 'USPAT2' ENTERED AT 16:03:03 ON 10 JUN 2003
CA INDEXING COPYRIGHT (C) 2003 AMERICAN CHEMICAL SOCIETY (ACS)

=> d his

     (FILE 'HOME' ENTERED AT 15:58:22 ON 10 JUN 2003)

     FILE 'REGISTRY' ENTERED AT 15:58:43 ON 10 JUN 2003
L1             0 S GAMMA-BUTROLACTONE
L2           422 S GAMMA-BUTYROLACTONE

     FILE 'REGISTRY' ENTERED AT 16:00:16 ON 10 JUN 2003
L3               STR 195000-66-9
L4             0 S L3 EXA SAM

     FILE 'REGISTRY' ENTERED AT 16:00:32 ON 10 JUN 2003
L5             1 S 195000-66-9/RN
                 SET NOTICE 1 DISPLAY
                 SET NOTICE LOGIN DISPLAY

     FILE 'REGISTRY' ENTERED AT 16:01:26 ON 10 JUN 2003

     FILE 'REGISTRY' ENTERED AT 16:02:03 ON 10 JUN 2003
L6             2 S GAMMA-BUTYROLACTONE METHACRYLATE
L7             7 S 2-METHYLADAMANTYL METHACRYLATE
L8             1 S L6 AND L7

     FILE 'CAPLUS, HCAPLUS, USPATFULL, USPAT2' ENTERED AT 16:03:03 ON 10 JUN
     2003

=> s l8
L9            95 L8

=> FIL HOME
COST IN U.S. DOLLARS                                SINCE FILE      TOTAL
                                                         ENTRY    SESSION
FULL ESTIMATED COST                                       5.25      66.38

FILE 'HOME' ENTERED AT 16:03:21 ON 10 JUN 2003

=> file reg
COST IN U.S. DOLLARS                                SINCE FILE      TOTAL
```

```
                                                          ENTRY    SESSION
FULL ESTIMATED COST                                        1.89      68.27

FILE 'REGISTRY' ENTERED AT 16:08:51 ON 10 JUN 2003
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Property values tagged with IC are from the ZIC/VINITI data file
provided by InfoChem.

STRUCTURE FILE UPDATES:    9 JUN 2003  HIGHEST RN 528266-88-8
DICTIONARY FILE UPDATES:   9 JUN 2003  HIGHEST RN 528266-88-8

TSCA INFORMATION NOW CURRENT THROUGH JANUARY 6, 2003

  Please note that search-term pricing does apply when
  conducting SmartSELECT searches.

Crossover limits have been increased.  See HELP CROSSOVER for details.

Experimental and calculated property data are now available.  See HELP
PROPERTIES for more information.  See STNote 27, Searching Properties
in the CAS Registry File, for complete details:
http://www.cas.org/ONLINE/STN/STNOTES/stnotes27.pdf

=> ....Testing the current file.... screen

ENTER SCREEN EXPRESSION OR (END):end


=> screen 963 AND 1006

L10   SCREEN CREATED

=>
Uploading C:\Program Files\Stnexp\Queries\09940665.str

L11     STRUCTURE UPLOADED

=> que L11 AND L10

L12  QUE L11 AND L10

=> d
L12 HAS NO ANSWERS
L10             SCR 963 AND 1006
L11             STR

*** STRUCTURE DIAGRAM IS NOT AVAILABLE ***

Structure attributes must be viewed using STN Express query preparation.
L12             QUE  ABB=ON  PLU=ON  L11 AND L10


=> s l12
SAMPLE SEARCH INITIATED 16:09:15 FILE 'REGISTRY'
SAMPLE SCREEN SEARCH COMPLETED -     28 TO ITERATE

100.0% PROCESSED      28 ITERATIONS                              0 ANSWERS
SEARCH TIME: 00.00.01

FULL FILE PROJECTIONS:  ONLINE  **COMPLETE**
                        BATCH   **COMPLETE**
```

```
PROJECTED ITERATIONS:          243 TO      877
PROJECTED ANSWERS:               0 TO        0

L13           0 SEA SSS SAM L11 AND L10

=> s l12 sss sam
SAMPLE SEARCH INITIATED 16:09:19 FILE 'REGISTRY'
SAMPLE SCREEN SEARCH COMPLETED -     28 TO ITERATE

100.0% PROCESSED      28 ITERATIONS                                0 ANSWERS
SEARCH TIME: 00.00.01

FULL FILE PROJECTIONS:  ONLINE  **COMPLETE**
                        BATCH   **COMPLETE**
PROJECTED ITERATIONS:          243 TO      877
PROJECTED ANSWERS:               0 TO        0

L14           0 SEA SSS SAM L11 AND L10

=> FIL CAPLUS HCAPLUS USPATFULL USPAT2
COST IN U.S. DOLLARS                        SINCE FILE      TOTAL
                                               ENTRY    SESSION
FULL ESTIMATED COST                             0.40      68.67

FILE 'CAPLUS' ENTERED AT 16:09:23 ON 10 JUN 2003
USE IS SUBJECT TO THE TERMS OF YOUR STN CUSTOMER AGREEMENT.
PLEASE SEE "HELP USAGETERMS" FOR DETAILS.
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FILE 'HCAPLUS' ENTERED AT 16:09:23 ON 10 JUN 2003
USE IS SUBJECT TO THE TERMS OF YOUR STN CUSTOMER AGREEMENT.
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FILE 'USPATFULL' ENTERED AT 16:09:23 ON 10 JUN 2003
CA INDEXING COPYRIGHT (C) 2003 AMERICAN CHEMICAL SOCIETY (ACS)

FILE 'USPAT2' ENTERED AT 16:09:23 ON 10 JUN 2003
CA INDEXING COPYRIGHT (C) 2003 AMERICAN CHEMICAL SOCIETY (ACS)

=> s l14
L15           0 L14

=> d his

     (FILE 'HOME' ENTERED AT 15:58:22 ON 10 JUN 2003)

     FILE 'REGISTRY' ENTERED AT 15:58:43 ON 10 JUN 2003
L1            0 S GAMMA-BUTROLACTONE
L2          422 S GAMMA-BUTYROLACTONE

     FILE 'REGISTRY' ENTERED AT 16:00:16 ON 10 JUN 2003
L3              STR 195000-66-9
L4            0 S L3 EXA SAM

     FILE 'REGISTRY' ENTERED AT 16:00:32 ON 10 JUN 2003
L5            1 S 195000-66-9/RN
                SET NOTICE 1 DISPLAY
                SET NOTICE LOGIN DISPLAY

     FILE 'REGISTRY' ENTERED AT 16:01:26 ON 10 JUN 2003

     FILE 'REGISTRY' ENTERED AT 16:02:03 ON 10 JUN 2003
L6            2 S GAMMA-BUTYROLACTONE METHACRYLATE
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L7             7 S 2-METHYLADAMANTYL METHACRYLATE
L8             1 S L6 AND L7

     FILE 'CAPLUS, HCAPLUS, USPATFULL, USPAT2' ENTERED AT 16:03:03 ON 10 JUN
     2003
L9            95 S L8

     FILE 'HOME' ENTERED AT 16:03:21 ON 10 JUN 2003

     FILE 'REGISTRY' ENTERED AT 16:08:51 ON 10 JUN 2003
L10              SCREEN 963 AND 1006
L11              STRUCTURE UPLOADED
L12              QUE L11 AND L10
L13            0 S L12
L14            0 S L12 SSS SAM

     FILE 'CAPLUS, HCAPLUS, USPATFULL, USPAT2' ENTERED AT 16:09:23 ON 10 JUN
     2003
L15            0 S L14

=> s l9 and l15
L16            0 L9 AND L15

=> s l9 and (resist or photoresist)
L17           95 L9 AND (RESIST OR PHOTORESIST)

=> s l17 and (?acid generator)
L18           77 L17 AND (?ACID GENERATOR)

=> s (?5active)
L19            7 (?5ACTIVE)

=> s l18 and acetal
L20           12 L18 AND ACETAL

=> duplicates remove
ENTER L# LIST OR (END):l20
DUPLICATE PREFERENCE IS 'CAPLUS, HCAPLUS, USPATFULL, USPAT2'
KEEP DUPLICATES FROM MORE THAN ONE FILE?  Y/(N):n
PROCESSING COMPLETED FOR L20
L21            8 DUPLICATE REMOVE L20 (4 DUPLICATES REMOVED)

=> d l21 1-8 ibib abs hitstr

L21  ANSWER 1 OF 8  USPATFULL
ACCESSION NUMBER:        2003:120442  USPATFULL
TITLE:                   Pattern formation method
INVENTOR(S):             Endo, Masayuki, Osaka, JAPAN
                         Sasago, Masaru, Osaka, JAPAN
PATENT ASSIGNEE(S):      Matsushita Electric Industrial Co., Ltd., Osaka, JAPAN,
                         571-8501 (non-U.S. corporation)

                              NUMBER        KIND    DATE
                         ---------------- ------ --------
PATENT INFORMATION:      US 2003082926      A1   20030501
APPLICATION INFO.:       US 2002-279070     A1   20021024  (10)

                                NUMBER         DATE
                         ------------------ --------
PRIORITY INFORMATION:    JP 2001-334168     20011031
DOCUMENT TYPE:           Utility
FILE SEGMENT:            APPLICATION
LEGAL REPRESENTATIVE:    NIXON PEABODY, LLP, 8180 GREENSBORO DRIVE, SUITE 800,
                         MCLEAN, VA, 22102
```

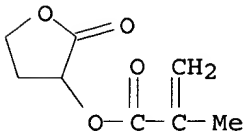
10-04-02

NUMBER OF CLAIMS: 12
EXEMPLARY CLAIM: 1
NUMBER OF DRAWINGS: 3 Drawing Page(s)
LINE COUNT: 715
CAS INDEXING IS AVAILABLE FOR THIS PATENT.
AB A **resist** film is formed from a chemically amplified **resist** material including a base polymer having a protecting group released by a function of an acid, an acrylic compound and an **acid generator** that generates an acid when irradiated with light. The **resist** film is selectively irradiated with exposing light for pattern exposure, and is developed after the pattern exposure so as to form a **resist** pattern having a hole or groove opening. The size of the opening is reduced by irradiating the **resist** pattern with light with annealing.

CAS INDEXING IS AVAILABLE FOR THIS PATENT.
IT **195000-67-0**
(pattern formation method contg.)
RN 195000-67-0 USPATFULL
CN 2-Propenoic acid, 2-methyl-, 2-methyltricyclo[3.3.1.13,7]dec-2-yl ester, polymer with tetrahydro-2-oxo-3-furanyl 2-methyl-2-propenoate (9CI) (CA INDEX NAME)

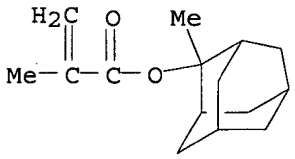
CM 1

CRN 195000-66-9
CMF C8 H10 O4



CM 2

CRN 177080-67-0
CMF C15 H22 O2



L21 ANSWER 2 OF 8 CAPLUS COPYRIGHT 2003 ACS DUPLICATE 1
ACCESSION NUMBER: 2002:794184 CAPLUS
DOCUMENT NUMBER: 137:317925
TITLE: Chemically amplified **resist** composition and method for forming patterned film using same
INVENTOR(S): Yamamoto, Hajime; Murakami, Kenichi; Takechi, Satoshi
PATENT ASSIGNEE(S): Fujitsu Limited, Japan
SOURCE: U.S. Pat. Appl. Publ., 10 pp.
CODEN: USXXCO
DOCUMENT TYPE: Patent
LANGUAGE: English
FAMILY ACC. NUM. COUNT: 1

PATENT INFORMATION:

present appl.

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
US 2002150834	A1	20021017	US 2001-940665 →	20010829
JP 2002311587	A2	20021023	JP 2001-111740	20010410
DE 10147011	A1	20021107	DE 2001-10147011	20010925

PRIORITY APPLN. INFO.: JP 2001-111740 A 20010410

AB The present invention relates to a chem. amplified **resist** compn. which comprises (1) a base resin reacting in the presence of an acid, (2) a photo **acid generator** generating an acid upon exposure, and (3) a compd. having the combination of an **acetal** moiety and a site which is eliminated by an acid in its mol., or which comprises (1) a base resin, which is a copolymer having the combination of an **acetal** moiety and a site eliminated by an acid in one repeating unit and reacts in the presence of an acid, and (2) a photo **acid generator** generating an acid upon exposure. The present invention relates to a chem. amplified **resist** compn., which is a radiation-sensitive material used in the manuf. of semiconductor devices, and method for forming a patterned film using the **resist** compn.

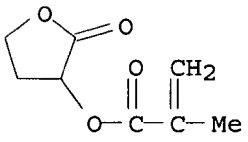
IT **195000-67-0**
RL: PRP (Properties); TEM (Technical or engineered material use); USES (Uses)
(chem. amplified **photoresist** compn. for lithog. patterning contg.)

RN 195000-67-0 CAPLUS

CN 2-Propenoic acid, 2-methyl-, 2-methyltricyclo[3.3.1.13,7]dec-2-yl ester, polymer with tetrahydro-2-oxo-3-furanyl 2-methyl-2-propenoate (9CI) (CA INDEX NAME)

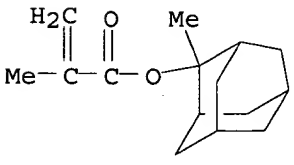
CM 1

CRN 195000-66-9
CMF C8 H10 O4



CM 2

CRN 177080-67-0
CMF C15 H22 O2



L21 ANSWER 3 OF 8 USPATFULL DUPLICATE 2
ACCESSION NUMBER: 2002:156925 USPATFULL
TITLE: Chemical amplification type positive **resist** composition

INVENTOR(S): Uetani, Yasunori, Osaka, JAPAN
Inoue, Hiroki, Osaka, JAPAN
PATENT ASSIGNEE(S): Sumitomo Chemical Co., Ltd. (non-U.S. corporation)

	NUMBER	KIND	DATE
PATENT INFORMATION:	US 2002081523	A1	20020627
	US 6548221	B2	20030415
APPLICATION INFO.:	US 2001-3441	A1	20011206 (10)

RELATED APPLN. INFO.: Division of Ser. No. US 2000-482359, filed on 14 Jan 2000, PENDING

	NUMBER	DATE
PRIORITY INFORMATION:	JP 1999-9096	19990118

DOCUMENT TYPE: Utility
FILE SEGMENT: APPLICATION
LEGAL REPRESENTATIVE: BIRCH STEWART KOLASCH & BIRCH, PO BOX 747, FALLS CHURCH, VA, 22040-0747
NUMBER OF CLAIMS: 8
EXEMPLARY CLAIM: 1
LINE COUNT: 788
CAS INDEXING IS AVAILABLE FOR THIS PATENT.

AB A positive **resist** composition is provided which comprises a resin having 2-alkyl-2-adamantyl (meth)acrylate polymerization unit represented by the following formula (I): ##STR1##

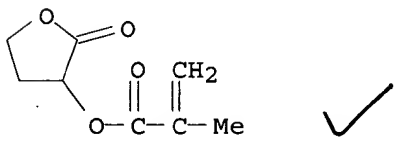
wherein R.sup.1 represents hydrogen or methyl and R.sup.2 represents an alkyl, and being insoluble or barely soluble in alkali, but being converted to soluble in alkali by the action of an and an **acid generator** represented by the following formula (V): ##STR2##

wherein Q.sup.1, Q.sup.2 and Q.sup.3 independently represent hydrogen, a hydroxyl group, an alkyl having 1 to 6 carbon atoms or an alkoxy having 1 to 6 carbon atoms, and n is an integer of 4 to 8; and gives a good resolution upon exposure by ArP excimer laser and has little substrate dependency.

CAS INDEXING IS AVAILABLE FOR THIS PATENT.
IT **195000-67-0P**
(chem. amplification-type pos. resist compn.)
RN 195000-67-0 USPATFULL
CN 2-Propenoic acid, 2-methyl-, 2-methyltricyclo[3.3.1.13,7]dec-2-yl ester, polymer with tetrahydro-2-oxo-3-furanyl 2-methyl-2-propenoate (9CI) (CA INDEX NAME)

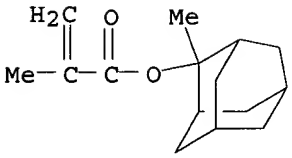
CM 1

CRN 195000-66-9
CMF C8 H10 O4



CM 2

CRN 177080-67-0
CMF C15 H22 O2



L21 ANSWER 4 OF 8 USPATFULL DUPLICATE 3

ACCESSION NUMBER:	2002:99037 USPATFULL		
TITLE:	Positive photosensitive composition		
INVENTOR(S):	Kodama, Kunihiko, Shizuoka, JAPAN Aoai, Toshiaki, Shizuoka, JAPAN		
PATENT ASSIGNEE(S):	FUJI PHOTO FILM CO., LTD. (non-U.S. corporation)		

	NUMBER	KIND	DATE
PATENT INFORMATION:	US 2002051933	A1	20020502
	US 6492091	B2	20021210
APPLICATION INFO.:	US 2001-921691	A1	20010806 (9)

	NUMBER	DATE
PRIORITY INFORMATION:	JP 2000-240059	20000808

DOCUMENT TYPE:	Utility
FILE SEGMENT:	APPLICATION
LEGAL REPRESENTATIVE:	SUGHRUE, MION, ZINN, MACPEAK & SEAS, PLLC, 2100 Pennsylvania Avenue, N.W., Washington, DC, 20037
NUMBER OF CLAIMS:	20
EXEMPLARY CLAIM:	1
LINE COUNT:	2260

CAS INDEXING IS AVAILABLE FOR THIS PATENT.

AB A positive photosensitive composition comprises: (A) a compound generating an acid upon irradiation with one of an actinic ray and radiation; (B) a resin containing a monocyclic or polycyclic alicyclic hydrocarbon structure and increasing the solubility to an alkali developer by the action of an acid; and (C) an onium salt of carboxylic acid.

CAS INDEXING IS AVAILABLE FOR THIS PATENT.

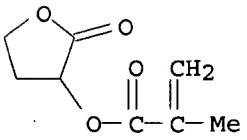
IT **195000-67-0P**
(resin; deep UV photofabrication pos. photoresist compn. contg.)

RN 195000-67-0 USPATFULL

CN 2-Propenoic acid, 2-methyl-, 2-methyltricyclo[3.3.1.13,7]dec-2-yl ester, polymer with tetrahydro-2-oxo-3-furanyl 2-methyl-2-propenoate (9CI) (CA INDEX NAME)

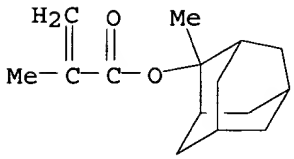
CM 1

CRN 195000-66-9
CMF C8 H10 O4



CM 2

CRN 177080-67-0
CMF C15 H22 O2



L21 ANSWER 5 OF 8 USPATFULL

ACCESSION NUMBER:	2002:191427 USPATFULL
TITLE:	Positive photosensitive composition
INVENTOR(S):	Kodama, Kunihiko, Shizuoka, JAPAN Aoai, Toshiaki, Shizuoka, JAPAN
PATENT ASSIGNEE(S):	FUJI PHOTO FILM CO., LTD. (non-U.S. corporation)

	NUMBER	KIND	DATE
PATENT INFORMATION:	US 2002102491	A1	20020801
APPLICATION INFO.:	US 2001-978103	A1	20011017 (9)

	NUMBER	DATE
PRIORITY INFORMATION:	JP 2000-321128	20001020
	JP 2000-352899	20001120
	JP 2001-132546	20010427

DOCUMENT TYPE:	Utility
FILE SEGMENT:	APPLICATION
LEGAL REPRESENTATIVE:	SUGHRUE, MION, ZINN, MACPEAK & SEAS, PLLC, 2100 Pennsylvania Avenue, N.W., Washington, DC, 20037
NUMBER OF CLAIMS:	18
EXEMPLARY CLAIM:	1
LINE COUNT:	2767

CAS INDEXING IS AVAILABLE FOR THIS PATENT.

AB A positive photosensitive composition comprises a compound capable of generating a specified sulfonic acid upon irradiation with one of an actinic ray and radiation and (B) a resin capable of decomposing under the action of an acid to increase the solubility in an alkali developer.

CAS INDEXING IS AVAILABLE FOR THIS PATENT.

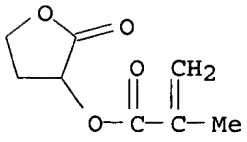
IT **195000-67-0**
(photo-acid generator used in pos. photoresist compn.)

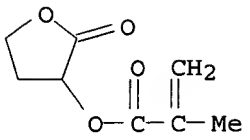
RN 195000-67-0 USPATFULL

CN 2-Propenoic acid, 2-methyl-, 2-methyltricyclo[3.3.1.13,7]dec-2-yl ester, polymer with tetrahydro-2-oxo-3-furanyl 2-methyl-2-propenoate (9CI) (CA INDEX NAME)

CM 1

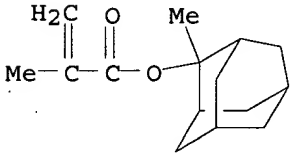
CRN 195000-66-9
CMF C8 H10 O4





CM 2

CRN 177080-67-0
CMF C15 H22 O2



L21 ANSWER 6 OF 8 USPATFULL

ACCESSION NUMBER:	2002:102236 USPATFULL
TITLE:	Chemical amplification type positive **resist** composition
INVENTOR(S):	Uetani, Yasunori, Toyonaka, JAPAN Inoue, Hiroki, Toyonaka, JAPAN
PATENT ASSIGNEE(S):	Sumitomo Chemical Company, Limited, Osaka, JAPAN (non-U.S. corporation)

	NUMBER	KIND	DATE
PATENT INFORMATION:	US 6383713	B1	20020507
APPLICATION INFO.:	US 2000-482359		20000114 (9)

	NUMBER	DATE
PRIORITY INFORMATION:	JP 1999-9096	19990118

DOCUMENT TYPE:	Utility
FILE SEGMENT:	GRANTED
PRIMARY EXAMINER:	Ashton, Rosemary
LEGAL REPRESENTATIVE:	Birch Stewart Kolasch & Birch LLP
NUMBER OF CLAIMS:	2
EXEMPLARY CLAIM:	1
NUMBER OF DRAWINGS:	0 Drawing Figure(s); 0 Drawing Page(s)
LINE COUNT:	776

CAS INDEXING IS AVAILABLE FOR THIS PATENT.

AB A positive **resist** composition is provided which comprises a resin having 2-alkyl-2-adamantyl (meth)acrylate polymerization unit represented by the following formula (I): ##STR1##

wherein R.sup.1 represents hydrogen or methyl and R.sup.2 represents an alkyl, and being insoluble or barely soluble in alkali, but being converted to soluble in alkali by the action of an acid;

and an **acid generator** represented by the following formula (V): ##STR2##

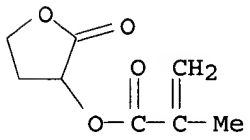
wherein Q.sup.1, Q.sup.2 and Q.sup.3 independently represent hydrogen, a hydroxyl group, an alkyl having 1 to 6 carbon atoms or an alkoxy having 1 to 6 carbon atoms, and n is an integer of 4 to 8. The composition exhibits good resolution upon exposure by a ArP excimer laser and has

little substrate dependency.

CAS INDEXING IS AVAILABLE FOR THIS PATENT.
IT **195000-67-0P**
(chem. amplification-type pos. resist compn.)
RN 195000-67-0 USPATFULL
CN 2-Propenoic acid, 2-methyl-, 2-methyltricyclo[3.3.1.13,7]dec-2-yl ester, polymer with tetrahydro-2-oxo-3-furanyl 2-methyl-2-propenoate (9CI) (CA INDEX NAME)

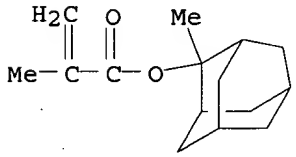
CM 1

CRN 195000-66-9
CMF C8 H10 O4



CM 2

CRN 177080-67-0
CMF C15 H22 O2



L21 ANSWER 7 OF 8 USPATFULL

ACCESSION NUMBER:	2002:34281 USPATFULL
TITLE:	Chemical amplification type positive **resist**
INVENTOR(S):	Uetani, Yasunori, Toyonaka, JAPAN Oohashi, Kenji, Yawata, JAPAN Inoue, Hiroki, Toyonaka, JAPAN
PATENT ASSIGNEE(S):	Sumitomo Chemical Company, Limited, Osaka, JAPAN (non-U.S. corporation)

	NUMBER	KIND	DATE	
PATENT INFORMATION:	US 6348297	B1	20020219	
APPLICATION INFO.:	US 2000-533986		20000324	(9)

	NUMBER	DATE
PRIORITY INFORMATION:	JP 1999-92990	19990331
	JP 1999-315264	19991105

DOCUMENT TYPE:	Utility
FILE SEGMENT:	GRANTED
PRIMARY EXAMINER:	Ashton, Rosemary
LEGAL REPRESENTATIVE:	Birch, Stewart, Kolasch & Birch, LLP
NUMBER OF CLAIMS:	16
EXEMPLARY CLAIM:	1
NUMBER OF DRAWINGS:	0 Drawing Figure(s); 0 Drawing Page(s)

LINE COUNT: 1138
CAS INDEXING IS AVAILABLE FOR THIS PATENT.
AB A chemical amplification type positive **resist** composition which is good in resolution, provide a good pattern profile under exposure using light of wavelength of 220 nm or shorter even when applied on a basic substrate or a low reflectance substrate and which comprises an **acid generator** comprising an aliphatic sulfonium salt represented by the following formula (I): ##STR1##

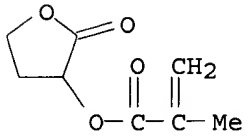
wherein Q.sup.1 represents an alkyl group, Q.sup.2 represents an alkyl or a residue of an alicyclic hydrocarbon and m represents an integer of 1 to 8; and onium salt selected from triphenylsulfonium salts represented by the following formula (IIa) and diphenyliodonium salts represented by the following formula (IIb): ##STR2##

wherein Q.sup.3, Q.sup.4, Q.sup.5, Q.sup.6 and Q.sup.7each independently represent a hydrogen atom, a hydroxyl group, an alkyl group having 1 to 6 carbon atoms, an alkoxy group having 1 to 6 carbon atoms, and q and p represent a integer of 4 to 8; and (2) a resin which has a polymerization unit with a group unstable to an acid, and is insoluble or barely soluble in alkali by itself but changes soluble in alkali by an action of the acid, is provided.

CAS INDEXING IS AVAILABLE FOR THIS PATENT.
IT **195000-67-0P**, .alpha.-Methacryloyloxy-.gamma.-butyrolactone-2-methyl-2-adamantyl methacrylate copolymer
(manuf. of resin for chem.-amplified pos. resist contg.)
RN 195000-67-0 USPATFULL
CN 2-Propenoic acid, 2-methyl-, 2-methyltricyclo[3.3.1.13,7]dec-2-yl ester, polymer with tetrahydro-2-oxo-3-furanyl 2-methyl-2-propenoate (9CI) (CA INDEX NAME)

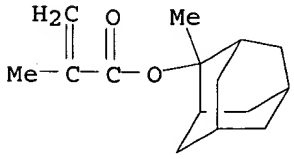
CM 1

CRN 195000-66-9
CMF C8 H10 O4



CM 2

CRN 177080-67-0
CMF C15 H22 O2



L21 ANSWER 8 OF 8 USPATFULL
ACCESSION NUMBER: 2001:79255 USPATFULL
TITLE: Chemical amplifying type positive **resist**

composition

INVENTOR(S): Fujishima, Hiroaki, Toyonaka, Japan
Uetani, Yasunori, Toyonaka, Japan
Araki, Karou, Kyoto, Japan

PATENT ASSIGNEE(S): Sumitomo Chemical, Company Limited, Osaka, Japan
(non-U.S. corporation)

	NUMBER	KIND	DATE
PATENT INFORMATION:	US 6239231	B1	20010529
APPLICATION INFO.:	US 1999-384032		19990826 (9)

	NUMBER	DATE
PRIORITY INFORMATION:	JP 1998-240143	19980826

DOCUMENT TYPE: Utility
FILE SEGMENT: Granted
PRIMARY EXAMINER: Lipman, Bernard
LEGAL REPRESENTATIVE: Birch, Stewart, Kolasch & Birch, LLP
NUMBER OF CLAIMS: 16
EXEMPLARY CLAIM: 1
LINE COUNT: 860
CAS INDEXING IS AVAILABLE FOR THIS PATENT.

AB A chemical amplifying type positive **resist** composition, excellent in adhesion to a substrate and good in **resist** performances and suitable for exposure using a KrF excimer laser, ArF excimer laser, or the like, which comprises a resin having a polymerization unit of 2-alkyl-2-adamantyl (meth)acrylate and a polymerization unit of a monomer selected from 3-hydroxy-1-adamantyl (meth)acrylate and (meth)acrylonitrile, and an **acid generator** is provided.

CAS INDEXING IS AVAILABLE FOR THIS PATENT.

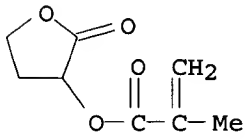
IT **195000-67-0P**
(prepn. and use in prepg. chem. amplified pos. photoresists)

RN 195000-67-0 USPATFULL

CN 2-Propenoic acid, 2-methyl-, 2-methyltricyclo[3.3.1.13,7]dec-2-yl ester, polymer with tetrahydro-2-oxo-3-furanyl 2-methyl-2-propenoate (9CI) (CA INDEX NAME)

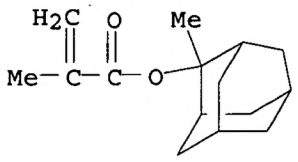
CM 1

CRN 195000-66-9
CMF C8 H10 O4

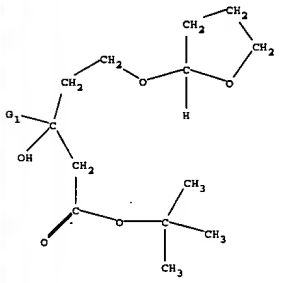


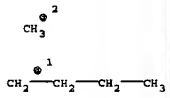
CM 2

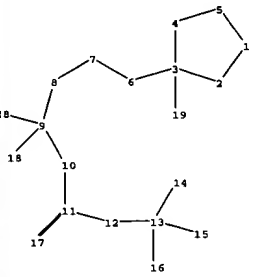
CRN 177080-67-0
CMF C15 H22 O2

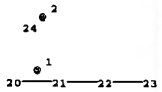

H2C
O
Me
Me
C
C
O

C:\Program Files\Stnexp\Queries\09940665.str









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ring nodes :
1 2 3 4 5
chain bonds :
3-6 3-19 6-7 7-8 8-9 9-10 9-18 9-28 10-11 11-12 11-17 12-13 13-14 13-15 13-16
20-21 21-22 22-23
ring bonds :
1-2 1-5 2-3 3-4 4-5
exact/norm bonds :
1-2 1-5 2-3 3-4 3-6 4-5 9-18 9-28 11-12 11-17 12-13
exact bonds :
3-19 6-7 7-8 8-9 9-10 10-11 13-14 13-15 13-16 20-21 21-22 22-23

G1:[*1],[*2]

Match level :
1:Atom 2:Atom 3:Atom 4:Atom 5:Atom 6:CLASS 7:CLASS 8:CLASS 9:CLASS 10:CLASS
11:CLASS 12:CLASS 13:CLASS 14:CLASS 15:CLASS 16:CLASS 17:CLASS 18:CLASS 19:CLASS
20:CLASS 21:CLASS 22:CLASS 23:CLASS 24:CLASS 28:CLASS

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Uploading C:\Program Files\Stnexp\Queries\09940665.str

L22     STRUCTURE UPLOADED

=> que L22

L23  QUE L22

=> d
L23 HAS NO ANSWERS
L22             STR

*** STRUCTURE DIAGRAM IS NOT AVAILABLE ***

Structure attributes must be viewed using STN Express query preparation.
L23             QUE  ABB=ON  PLU=ON  L22


=> s l23 sss sam
SAMPLE SEARCH INITIATED 16:13:24 FILE 'REGISTRY'
SAMPLE SCREEN SEARCH COMPLETED -     35 TO ITERATE

100.0% PROCESSED      35 ITERATIONS                                0 ANSWERS
SEARCH TIME: 00.00.01

FULL FILE PROJECTIONS:  ONLINE  **COMPLETE**
                        BATCH   **COMPLETE**
PROJECTED ITERATIONS:          346 TO     1054
PROJECTED ANSWERS:               0 TO        0

L24           0 SEA SSS SAM L22

=> FIL CAPLUS HCAPLUS USPATFULL USPAT2
COST IN U.S. DOLLARS                                SINCE FILE      TOTAL
                                                       ENTRY    SESSION
FULL ESTIMATED COST                                     0.40     126.12

DISCOUNT AMOUNTS (FOR QUALIFYING ACCOUNTS)          SINCE FILE      TOTAL
                                                       ENTRY    SESSION
CA SUBSCRIBER PRICE                                     0.00      -0.65

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=> s l24
L25           0 L24
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